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**REPLY UNDER 37 CFR 1.116  
EXPEDITED PROCEDURE  
TECHNOLOGY CENTER 2800**

**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

<b>In Re Application of:</b> Divakaruni et al.	<b>Conf. No.:</b> 1387
<b>Serial No.:</b> 10/707,388	<b>Art Unit:</b> 2891
<b>Filed:</b> 12/10/2003	<b>Examiner:</b> Fulk, Steven J.
<b>Title:</b> SILICIDE RESISTOR IN BEOL LAYER OF SEMICONDUCTOR DEVICE AND METHOD	<b>Docket No.:</b> FIS920030274 (IBMF-0032)

Mail Stop AF  
Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

**AFTER-FINAL REQUEST FOR RECONSIDERATION**

Sir:

**I. INTRODUCTORY COMMENTS:**

In response to the Final Office Action of December 07, 2006, please reconsider the above-referenced patent application in view of the following remarks: